

IN THE SPECIFICATION

Please insert the following paragraph on page 1, line 4:

This application is a continuation application of and claims priority to, Application Serial No. 09/926,676, filed on November 30, 2001, which is a national stage application of the International Bureau in PCT Application No. PCT/JP00/03597, filed on June 2, 2000. The entire contents of which are incorporated herein by reference.

Please amend the Abstract as follows:

ABSTRACT

This invention is a vacuum processing apparatus comprising of a vacuum processing area (14) having a stage (16) on which a substrate to be processed (17) is mounted, and a carrier port (18) provided on a ~~peripheral~~ peripheral wall of a processing chamber (11) forming the vacuum processing area (14) and carrying the substrate (17) onto and off the stage (16), for generating plasma in the vacuum processing area (14) and subjecting the substrate (17) on the stage (16) to a plasma processing, wherein a shutter (20) closing the carrier port (18) to prevent the plasma from being disordered when the plasma is generated in the vacuum processing chamber is provided.